

Eaton/Axcelis NV10-160 Ion Implanter

The system includes the standard source/gas box, manual-load end station, console, vacuum system, multiple wafer disks, and a quantity of spare parts.

Specifications:

Manufacturer	Eaton / Axcelis
Model	NV10-160
Maximum implant energy	160 keV
Beam current range	0.5 - 8mA
Wafer sizes	3", 4", 5" 6" capable
End station	Manual load
Automatic wafer handling	No AT4
Source	Standard
Gas box	4 ELB strings
Vacuum	Dry pump + diffusion pump
Control system	Standard console
Location	Wilmington, MA
Operational status	Currently operational

Included Disks

- 4" 2-pt clamp (2)
- 6" Clampless (4)
- 4" Clampless (2)
- 6" Full Ring
- 4" Full Ring 0 deg.

- 4" Full Ring (4)
- 3" 2-pt
- 3" Full Ring

Spare Parts

- Ion Source (2)
- Manipulator (2)
- Flag Faraday (2)
- Source Bushing (2)
- Source Cooling Flange (2)
- Source Isolation Valve